

Method and device for measuring contamination of a surface of a component of a lithographic apparatus

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ABSTRACT

A measuring device for determining contamination of a surface of a component in an lithographic projection apparatus . The measuring device has a radiation transmitter device for projecting radiation on at least a part of said surface and a radiation receiver device for
10 receiving radiation from the component. A processor device is communicatively connected to the radiation receiver device, for deriving a property of received radiation and deriving a property of the contamination from this property of radiation.

Also a method for measuring properties of contamination of a surface of a component in a lithographic projection apparatus, comprising: projecting radiation on the surface;
15 receiving radiation from the component and deriving from the received radiation properties of the contamination

Figure 3